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Simulating Chemical Etching of Optical Fiber to create NSOM Probe using COMSOL Multiphysics[®]

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Introduction

Chemically etching optical fiber with HF forms cone shaped Nearfield scanning optical microscopy (NSOM) probe and the cone angle of probe is dependent on etching time.







Figure 1. (a) Schematic of chemical etching process of optical fiber, (b) SEM image of NSOM probe.

Numerical Model

(a)

Model simulates etching of SiO₂ at the interface of optical fiber-HF solution.

diffusion 2D model was simulated using Transport of Species Diluted (tds) and Laminar Flow (spf) interfaces. Movement of etch front was implemented using Deformed Geometry (dg) interface. Geometry of the model consists of the following:



40% HF Solution

◀ 1 mm − 1

Schematic of

curvature of this outer surface increases.

Figure 3. Solution flow velocity.



- 40% HF solution
- Optical Fiber outer surface (2 mm above the solution)
- Figure 2. predefined etch form of Optical fiber in HF solution, (b) thickness 5 µm for enhanced 2D COMSOL model geometry. mesh movement

Governing Equations

Convection-Diffusion Equations:

(Transport of Diluted Species)

 $\frac{\sigma c_i}{\partial t} + \nabla \cdot \mathbf{J}_i + \mathbf{u} \cdot \nabla c_i = R_i$ $\mathbf{J}_i = -D_i \nabla c_i$

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HF Solution

(a)

$$\rho \frac{\partial \mathbf{u}}{\partial t} + \rho(\mathbf{u} \cdot \nabla)\mathbf{u} = \nabla \cdot \left[-\rho \mathbf{I} + \mathbf{K}\right] + \mathbf{F}$$

Conclusions

The deformed geometry from the simulated results suggest that the etching of optical fiber creates a cone shaped NSOM probe and the cone angle of the probe will become wider with increasing etching time. It has been observed experimentally that by increasing the etching time for optical fiber it is possible to create NSOM probes with wider cone angle.

Navier-Stokes equations: $\rho \nabla \cdot (\mathbf{u}) = 0$

(Laminar Flow)

$$\mathbf{K} = \boldsymbol{\mu} \Big(\nabla \mathbf{u} + (\nabla \mathbf{u})^{\mathsf{T}} \Big)$$

Diffusion Model

Etching Reaction: $SiO_2 + 6HF \longrightarrow H_2SiF_6 + 2H_2O$

Etch front movement (1st order reaction):

$$R = k \cdot c \qquad \qquad V_n = R \cdot K_D \qquad \qquad K_D = \frac{M_{si}}{m \cdot \rho_{si}}$$

where *R* – reaction rate at the interface HF solution-optical fiber

- k reaction rate constant, c HF solution concentration,
- *m* quantity of F atoms consumed for dissolution of one Si atom.

References

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